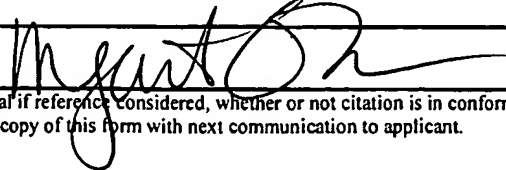


Substitute for form 1449A/PTO  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> (use as many sheets as necessary)				<b>Complete if Known</b>	
				Application Number	Unassigned
				Filing Date	Concurrently herewith
				First Named Inventor	Robert David ALLEN et al.
				Art Unit	Unassigned
				Examiner Name	Unassigned
Sheet	1	of	1	Attorney Docket Number	ARC920030072US1

U.S. PATENT DOCUMENTS							
Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
RPN	AA	5,047,492	9/10/91	Weidner et al.			
	AB	5,338,818	8/16/94	Brunsvold et al.			
	AC	5,385,804	1/31/95	Premilatha et al.			
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	AP	2003/0099899	5/29/03	Gronbeck et al.			
	AQ	2003/0108812	7/12/03	Rottstegge et al.			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS					T
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			
RPN	AR	FUJITA et al. (1996), "Nanometer-Scale Resolution of Calixarene Negative Resist in Electron Beam Lithography," <i>J. Vac. Sci. Technol. B</i> 14(6):4272-4276.			
	AS	KODAMA et al. (2002), "Synthesis of Novel Fluoropolymer for 157nm Photoresists by Cyclo-Polymerization," <i>Advances in Resist Technology and Processing XLX, Proceedings of SPIE 4690</i> :76-83.			
	AT	KUNZ et al. (2001), "Experimental VUV Absorbance Study of Fluorine-Functionalized Polystyrenes," <i>Advances in Resist Technology and Processing XVIII, Proceedings of SPIE 4345</i> :285-295.			
	AU	MANTZ et al. (1996), "Thermolysis of Polyhedral Oligomeric Silsesquioxane (POSS) Macromers and POSS-Siloxane Copolymers," <i>Chem. Mater.</i> 8(6):1250-1259.			
	AV	NAKAYAMA et al. (1997), "A Negative-Working Alkaline Developable Photoresist Based on Calix[4]resorcinarene, a Cross-Linker, and a Photoacid Generator," <i>Chemistry Letters</i> , pp. 265-266.			
	AW	OCHIAI et al. (1997), "High Resolution EB Lithography on Organic Resists: Molecular Size Effect," <i>Journal of Photopolymer Science and Technology</i> 10(4):641-646.			
	AX	TORIUMI et al. (2002), "Fluoropolymer Resists for 157-nm Lithography," <i>Advances in Resist Technology and Processing XLX, Proceedings of SPIE 4690</i> :191-199.			
	AY	YOSHIMURA et al. (1997), "Effects of Molecular-Weight Distributions of Resist Polymers and Process Control on Lithography for 0.1 $\mu$ m and Below," <i>Journal of Photopolymer Science and Technology</i> 10(4):629-634.			

Examiner Signature		Date Considered	3/17/06
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.